

## ABSTRACT

A substrate for an information recording medium,  
which has high heat resistance and high acid resistance and  
5 is formed of a glass having a glass transition temperature  
(T<sub>g</sub>) of 600°C or higher and having an etching rate of 0.1  
μm/minute or less with regard to a hydrosilicofluoric acid  
aqueous solution that is maintained at a temperature of  
45°C and has a hydrosilicofluoric acid concentration of  
10 1.72 % by weight, and an information recording medium  
having an information recording layer formed on the above  
substrate.